

In the Claims:

1.(Previously Amended) Oxide cathode comprising a support and an oxide layer on the support, wherein it furthermore includes particles of a conducting material having a first end incorporated in the support and a second end lodged in the oxide layer, so as to constitute conducting bridges passing through an interface layer forming between the support and the oxide layer.

2.(Previously Amended) Oxide cathode according to Claim 1, wherein the conducting material of the particles is a carbide of one or more metals.

3.(Previously Amended) Oxide cathode according to Claim 2, wherein the conducting material of the particles is a carbide of one or more metals of Group IVB, and preferably at least one metal from: titanium, zirconium and hafnium.

4.(Previously Amended) Oxide cathode according to Claim 2 wherein the conducting material of the particles is a carbide of one or more metals of Group VB, and preferably at least one metal from: vanadium, niobium and tantalum.

5.(Previously Amended) Oxide cathode according to Claim 2, wherein the conducting material of the particles is a carbide of one or more metals of Group VIB, and preferably at least one metal from: chromium, molybdenum and tungsten.

6.(Previously Amended) Oxide cathode according to Claim 1, wherein the support is made of metal, preferably a nickel-based metal.

7.(Previously Amended) Electron tube, wherein it comprises an oxide cathode according to Claim 1.

8.(Previously Amended) Cathode-ray tube, wherein it comprises an oxide cathode according to Claim 1.

9.(Currently Amended) Process for manufacturing an oxide cathode, in which an oxide layer is deposited on a support, the process comprising wherein it comprises the steps of consisting in:

- furnishing ~~that~~ a surface of the support which is intended to receive the oxide layer with particles of conducting material so that the particles have a first end incorporated in the support and a second end which is exposed; and
- covering said surface with an oxide layer.

10.(Currently Amended) Process according to Claim 9, wherein the step of furnishing the particles of conducting material consists in spreading out the particles over said surface and in applying a force to the particles in order to encrust said first end of the ~~latter~~ particles in the support.

11.(Previously Amended) Process according to Claim 9, wherein the step of furnishing the particles of conducting material consists in incorporating the particles in the support and in making said second end stand out from the support by a surface treatment, for example by means of a selective chemical etching treatment.

12.(Currently Amended) Process according to Claim 11, wherein the particles are incorporated in the support during the metallurgical production of the ~~latter~~ support.

13.(Previously Amended) Process according to Claim 11, in which the support is formed by drawing, wherein said second end of the particles is made to stand out before the drawing.

14.(Previously Amended) Process according to Claim 11, in which the support is formed by drawing, wherein said second end of the particles is made to stand out after the drawing.

15.(Previously Amended) Process according to Claim 9, wherein the conducting material of the particles is a carbide of one or more metals.

16.(Previously Amended) Process according to Claim 15, wherein the conducting material of the particles is a carbide of one or more metals of Group IVB, and preferably at least one metal from: titanium, zirconium and hafnium.

17.(Previously Amended) Process according to Claim 15 wherein the conducting material of the particles is a carbide of one or more metals of Group VB, and preferably at least one metal from: vanadium, niobium and tantalum.

18.(Previously Amended) Process according to Claim 15, wherein the conducting material of the particles is a carbide of one or more metals of Group VIB, and preferably at least one metal from: chromium, molybdenum and tungsten.

19.(Previously Amended) Process according to Claim 9, wherein the support is made of metal, preferably a nickel-based metal.